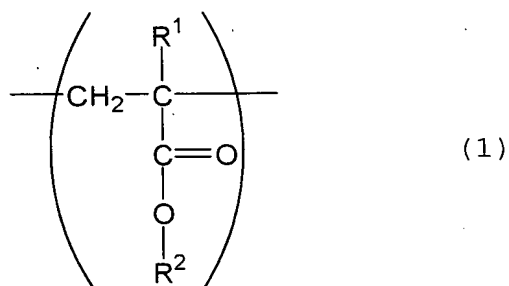


CLAIMS

- [1] A photosensitive fluororesin composition comprising (A) a copolymer having a fluorine atom in its molecule, (B) a compound having at least two alkyletherized amino groups in its molecule, (C) a photosensitive acid generating agent, and (D) a solvent.
- [2] The photosensitive fluororesin composition according to claim 1, wherein that said copolymer (A) having a fluorine atom in its molecule is a copolymer comprising
- (A1) a structural unit derived from at least one monomer selected from fluoro(meth)acrylic esters, fluoroolefins, and fluoroolefin derivatives and
- (A2) a structural unit derived from at least one monomer selected from hydroxyl-containing monomers, epoxy-containing monomers, and carboxyl-containing monomers.
- [3] The photosensitive fluororesin composition according to claim 2, wherein said copolymer (A) having a fluorine atom in its molecule further comprises
- (A3) a structural unit derived from at least one

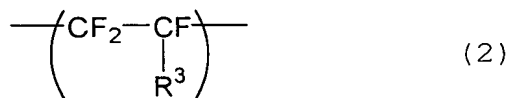
monomer selected from vinyl compounds, (meth)acrylic esters, unsaturated carboxylic acid esters, (meth)acrylamides, and unsaturated nitriles.

- [4] The photosensitive fluororesin composition according to claim 2, wherein said structural unit (A1) is a structural unit represented by formula (1):



wherein R^1 represents a hydrogen atom or a methyl group; and R^2 represents a fluoroalkyl group having 2 to 20 carbon atoms.

- [5] The photosensitive fluororesin composition according to claim 2, wherein said structural unit (A1) is a structural unit represented by formula (2):



wherein R^3 represents a fluorine atom, a perfluoroalkyl group having 1 to 10 carbon atoms, a perfluoroalkoxy group having 1 to 10 carbon atoms, or a chlorine atom.

- [6] The photosensitive fluororesin composition

according to claim 2, wherein said structural unit (A2) is a structural unit derived from a phenolic hydroxyl-containing monomer.

[7] The photosensitive fluororesin composition according to claim 1, wherein said copolymer (A) having a fluorine atom in its molecule further comprises a silicon atom.

[8] The photosensitive fluororesin composition according to claim 7, wherein said copolymer (A) having a fluorine atom in its molecule further comprises a siloxane structural unit represented by formula (3):



wherein R⁴ and R⁵ each independently represent a hydrogen atom, an alkyl group or a halogenated alkyl group having 1 to 10 carbon atoms, , or an aryl group having 6 to 20 carbon atoms.

[9] A cured film produced by curing a photosensitive fluororesin composition according to any of claims 1 to 8.

[10] A cured film comprising a pattern formed by curing a photosensitive fluororesin composition

according to any of claims 1 to 8.

[11] A method for pattern formation comprising the steps of: coating a photosensitive fluororesin composition according to any of claims 1 to 8 onto a support; drying the coating to form a coating film; exposing the coating film to light through a photomask; and then developing the exposed coating film with an alkaline developing solution.

[12] The method for pattern formation according to claim 11, wherein the exposure is carried out using an exposure light source with an irradiating light wavelength of 300 nm to 500 nm.

[13] A cured film having a pattern formed by a method for pattern formation according to claim 11.

[14] An anti-fouling film comprising a cured film according to claim 9.

[15] An anti-fouling film comprising a cured film according to claim 10.

[16] An anti-fouling film comprising a cured film according to claim 13.

[17] An article comprising on its surface a cured film according to claim 9.

[18] An article comprising on its surface a cured film according to claim 10.

[19] An anti-fouling article comprising on its surface
an anti-fouling film according to claim 14.

[20] An anti-fouling article comprising on its surface
an anti-fouling film according to claim 15.